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Figure S2: SEM Plane view of NiTiO₃ thin films deposited for 3 h at 550°C (a) and 650°C (b). The scale is indicated by the white bar. The thickness for each sample is estimated at 120 nm

Supplementary figures

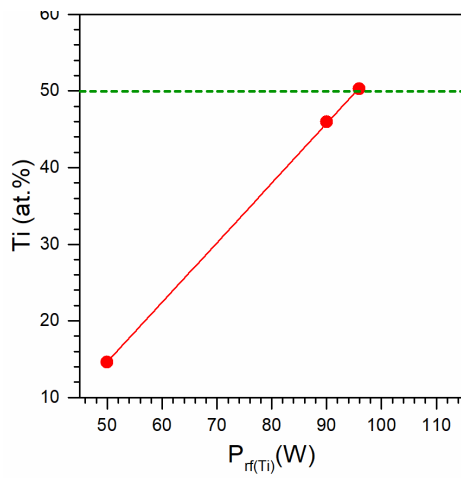


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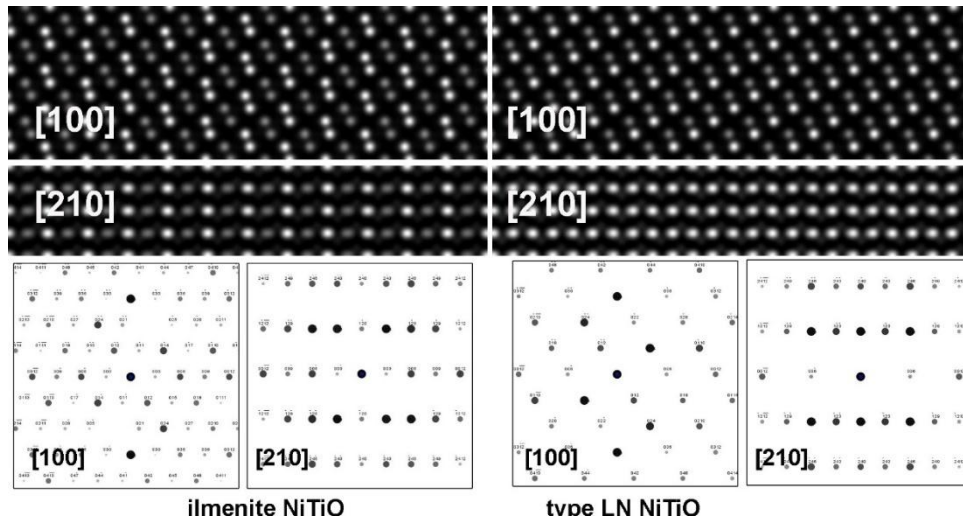


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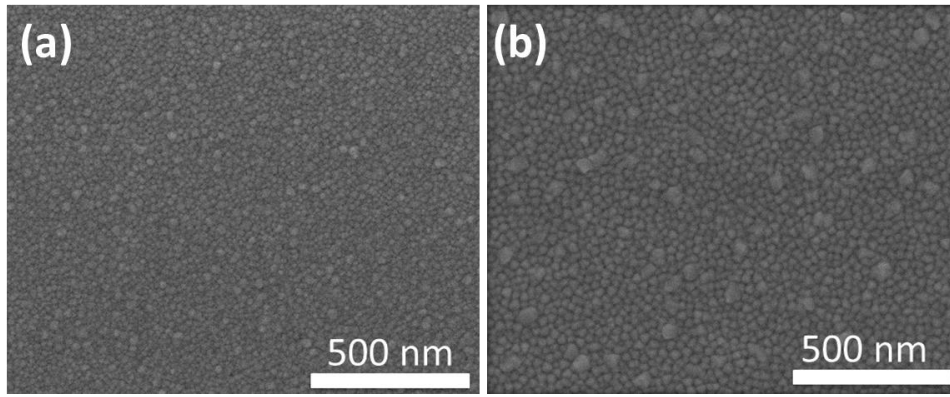


Figure S2: SEM Plane view of NiTiO₃ thin films deposited for 3 h at 550°C (a) and 650°C (b). The scale is indicated by the white bar. The thickness for each sample is estimated at 120 nm